

**Amendments to the Specification**

- 1) Please insert the following paragraph at page 1, line 3:

This application is a 371 of International PCT Application  
PCT/IB20204/004131, filed December 10, 2004.

- 2) Please replace the paragraphs beginning at page 1, line 22, and ending at  
page 2, line 6, with the following:

~~Patent Reference 1~~ US 6, 143, 192 describes the removal of ruthenium  
or solid ruthenium oxide (e.g., ruthenium dioxide) attached to the film-forming  
chamber by contact with aqueous ceric ammonium nitrate solution. However,  
wet methods such as this are inconvenient in terms of handling and also  
provide a low removal efficiency.

In contrast to this, ~~Patent Reference 2~~ JP 10-30439 describes a dry  
method that removes ruthenium metal as ruthenium tetroxide, a volatile  
compound. This is done by bringing the ruthenium metal deposited on the  
inner walls of the film-forming chamber into contact with an atomic oxygen-  
donating gas, such as ozone.

- 3) Please delete the text at page 2, lines 8-13, as follows:

~~Patent Reference 1~~

~~United States Patent Number 6,143,192~~

~~Patent Reference 2~~

~~Japanese Laid Open (Unexamined or Kokai or A) Patent Application Number  
Hei 10-30439 (30,439/1998)~~

- 4) Please insert the following paragraph at page 22, line 14:

It will be understood that many additional changes in the details,  
materials, steps and arrangement of parts, which have been herein described

in order to explain the nature of the invention, may be made by those skilled in the art within the principle and scope of the invention as expressed in the appended claims. Thus, the present invention is not intended to be limited to the specific embodiments in the examples given above.

- 5) Please replace the subtitle at page 23, line 1, with the following text:  
**CLAIMS** What is claimed is: